

AMENDMENT TRANSMITTAL LETTER						M4065.0210/P210		
Application No. 09/588,008		Filing Date June 6, 2000		Examiner Vikki H. Trinh		Art Unit 2814		
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Docket No.: M4065.0210/P2 (PATENT)

Group Art Unit: 2814

Examiner: Vikki H. Trinh

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Yang et al.

Application No.: 09/588,008

Filed: June 6, 2000

For: IMPROVED MEMORY CELL CAPACITOR

STRUCTURE AND METHOD OF

FORMATION

AMENDMENT

Commissioner for Patents Washington, DC 20231

Dear Sir:

This paper is in response to the Office Action dated December 26, 2002. Please amend the above-captioned U.S. Patent application as follows:

In the Claims:

Please rewrite claims 1, 26-28 and 98 as follows:

1. (twice amended) A capacitor for a semiconductor device, said capacitor comprising:

a bottom conducting layer;

a dielectric layer formed over said bottom conducting layer; and

an annealed top conducting layer formed over said dielectric layer, said top conducting layer comprising an oxygen permeable material.